

CLAIM AMENDMENTS

Claims 1-13 (Canceled).

14. (Previously Presented) A substrate treatment apparatus comprising:
a substrate heating device for maintaining a substrate at a temperature higher than room temperature;

a wetting device for producing a wet ozone-containing gas by wetting an ozone-containing gas with a treatment solution;

a supply device for supplying the wet ozone-containing gas from the wetting device to a work object on a surface of the substrate, said supply device comprising a gas disperser including a plurality of apertures aligned in a plurality of rows in a width direction of the work object, the apertures in adjacent rows not being aligned with each other in a direction perpendicular to the rows, and at least one of said gas disperser and the substrate being movable in a direction perpendicular to the rows;

a gas conduit connecting said wetting device to said supply device; and

a wet ozone-containing gas heating device for heating the wet ozone-containing gas a temperature at least equal to the temperature of the substrate.

Claim 15 (Canceled).

16. (Currently Amended) The substrate treatment assembly according to Claim ~~15~~ 14, wherein spacing between adjacent rows of apertures in said gas disperser is at least 5 mm.

17. (Previously Presented) A substrate treatment apparatus for supplying an ozone-containing gas and a treatment solution to a work object on a surface of a substrate, the assembly including a treatment agent supply plate facing the work object and through which the treatment solution is supplied, wherein a surface of the work object is spaced from said treatment agent supply plate by a distance in a range between 0.1 mm and 1.0 mm.